

Can molecular beam epitaxy be used as a solar absorber material?

Methods that are used to grow epitaxial III-V compound films, such as molecular beam epitaxy (MBE) or metal organic chemical vapour deposition (MOCVD) have revealed interesting features for fundamental studies like phase segregation and defect formation, but could not be used to form the absorber material for high-efficiency solar cells.

Does molecular beam epitaxy improve the performance of AlGaInP solar cells?

We demonstrate 2.0-2.2 eV AlGaInP solar cells grown by molecular beam epitaxy and their performance improvement by rapid thermal annealing (RTA). As grown, these cells exhibit lower performance than their counterparts grown by metal-organic vapor phase epitaxy (MOVPE), indicating a high concentration of point defects.

What is molecular beam epitaxy (MBE)?

Molecular Beam Epitaxy (MBE) represents a widely used growth technique to approach the basic research applied to the growth of semiconductor films and multilayer structures.

What is a molecular beam epitaxy system?

A molecular beam epitaxy system is basically a vacuum evaporation apparatus. What may be considered a standard MBE system is shown schematically in Fig. 2. Figure 1: (a) Structure of the 50 stacked quantum dot solar cell grown by MBE.

Which epitaxy is used in parallel to grow solar cells?

Jayaraman Theerthagiri, in Reference Module in Earth Systems and Environmental Sciences, 2023 Molecular beam epitaxy (MBE) and metal-organic vapor phase epitaxy (MOVPE) were used in parallel to grow solar cells with the homojunction of p-InGaN/n-InGaN and p-InGaN/i-InGaN/p-InGaN.

How thick is a 50 stacked quantum dot solar cell?

(a) Structure of the 50 stacked quantum dot solar cell grown by MBE. Each GaP layer has a nominal thickness of 1 ML = 0.273 nm. (b) Cross-sectional TEM image of the 50 stacked quantum dot layers. The arrows indicate the defects observable in the image (AIP license n. 2546451267415).

In this chapter, the solid-source molecular beam epitaxy (SS-MBE) growth of solar cells with phosphorus-based materials such as InGaP and InGaAsP, as well as the growth conditions to obtain high-quality tunnel junctions for the fabrication of multi-junction solar cells, are described. InGaP solar cells and InGaAsP solar cells grown ...

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We have investigated ~2.0 eV  $(\text{Al}_x\text{Ga}_{1-x})_{0.51}\text{In}_{0.49}\text{P}$  and ~1.9 eV  $\text{Ga}_{0.51}\text{In}_{0.49}\text{P}$  single junction solar cells grown on both on-axis and misoriented GaAs substrates by molecular beam epitaxy (MBE).

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We report on the molecular beam epitaxy (MBE) growth and device characteristics of Ge solar cells. Integrating a Ge bottom cell beneath a lattice-matched triple junction stack grown by MBE could enable ultra-high efficiencies without metamorphic growth or ...

We report abrupt Te doping of GaInP solar cells grown by molecular beam epitaxy (MBE) through the use of a low substrate temperature of 420 °C and subsequent ...

$(\text{Al}_x\text{Ga}_{1-x})_{0.51}\text{In}_{0.49}\text{P}$  (AlGaInP) is a promising top cell material for 5-6J devices due to its wide and tunable bandgap ( $E_g$ ). Moreover, 1.9-2.2 eV AlGaInP can be grown lattice-matched on GaAs, making it readily incorporable into the high-efficiency lattice-matched GaInP/GaAs/GaInNAsSb devices grown by molecular beam epitaxy (MBE). 3 Historically, the ...

In this work, we propose a novel efficient strategy based on the combination of molecular beam epitaxy deposition and the solid-state dewetting process for the growth and self-assembly of magnetic GeMn nanoparticles on the SiO<sub>2</sub> substrate.

We demonstrate 2.0-2.2 eV AlGaInP solar cells grown by molecular beam epitaxy and their performance improvement by rapid thermal annealing (RTA). As grown, these cells exhibit lower performance than their counterparts grown by metal-organic vapor phase epitaxy (MOVPE), indicating a high concentration of point defects. RTA improves ...

For high-efficiency Sb<sub>2</sub>(S,Se)<sub>3</sub> solar cells, the most commonly used electron-transporting layer of cadmium sulfide (CdS) is generally prepared by chemical bath deposition ...

Covers both the fundamentals and the state-of-the-art technology used for MBE Written by expert researchers working on the frontlines of the field, this book covers fundamentals of Molecular Beam Epitaxy (MBE) technology and science, as well as state-of-the-art MBE technology for electronic and optoelectronic device applications. MBE applications to magnetic ...

Molecular Beam Epitaxy (MBE) is a technology used for the deposition of thin film compound semiconductors, metals or insulators that allows a precise control of compositional profiles by...

Abstract: Triple-junction solar cells lattice-matched to InP have recently gained interest as an alternative to traditional GaAs-based devices. We predict a 1.74, 1.17, 0.70 eV device can attain high efficiency and can be achieved lattice-matched to InP. However, InAlAsSb, a relatively immature material, is required for the top junction. Here ...

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